



L Number	Hits	Search Text	DB	Time stamp
99	5889	(sicl4 sicl?sub.4 (silicon near tetrachloride)) same (vapor gas)	USPAT;	2002/12/27 07:57
			US-PGPUB;	
			ЕРО; ЈРО;	
			DERWENT	2002/12/27 00 02
100	12	((sicl4 sicl?sub.4 (silicon near tetrachloride)) same (vapor gas)) same	USPAT;	2002/12/27 08:02
		((relative near humifity) rh!)	US-PGPUB; EPO; JPO;	
			DERWENT	
101	50	428/426,446,447.ccls. and ((((silicon near (dioxide oxide)) siO siO2	USPAT;	2002/12/27 08:02
	50	sio?sub.2) same (layer coating)) same (humidity rh))	US-PGPUB;	2002/12/27 00:02
		(EPO; JPO;	
			DERWENT	
102	30	((sicl4 sicl?sub.4 (silicon near tetrachloride)) same (vapor gas)) same	USPAT;	2002/12/27 08:03
		((humidity) rh!)	US-PGPUB;	
			EPO; JPO;	,
			DERWENT	
103	18	(((sicl4 sicl?sub.4 (silicon near tetrachloride)) same (vapor gas)) same	USPAT;	2002/12/27 08:03
	!	((humidity) rh!)) not (((sicl4 sicl?sub.4 (silicon near tetrachloride)) same	US-PGPUB;	
		(vapor gas)) same ((relative near humifity) rh!))	EPO; JPO; DERWENT	
104	58	428/426,446,447.ccls. and ((((silicon near (dioxide oxide)) silica siO	USPAT;	2002/12/27 08:55
104	50	siO2 sio?sub.2) same (layer coating)) same haze)	US-PGPUB;	2002, 12,2, 00.55
		(4, 1, 1, 1, 1, 1, 1, 1, 1, 1, 1, 1, 1, 1,	EPO; JPO;	
			DERWENT	
105	6	("4019887" "4100330" "4144684" "4188444" "4385806"	USPAT	2002/12/27 08:46
		"4485146").PN.		
106	0	gb-705934-\$.did.	USPAT;	2002/12/27 08:55
			US-PGPUB;	
			EPO; JPO;	
107	0	uk-705934-\$.did.	DERWENT USPAT;	2002/12/27 08:55
107	U	uk-703934-9.did.	US-PGPUB;	2002/12/27 06.55
			EPO; JPO;	
			DERWENT	
108	14	"705934"	USPAT;	2002/12/27 08:55
			US-PGPUB;	
			EPO; JPO;	
			DERWENT	
109	79	(((silicon near (dioxide oxide)) silica siO siO2 sio?sub.2)) and (root near	USPAT;	2002/12/27 09:20
		mean near square near surface near roughness)	US-PGPUB;	
			EPO; JPO; DERWENT	
110	61	(((silicon near (dioxide oxide)) silica siO siO2 sio?sub.2) same (layer	USPAT;	2002/12/27 09:22
110	V-	coating)) and (root near mean near square near surface near roughness)	US-PGPUB;	
			EPO; JPO;	
			DERWENT	
111	18	((((silicon near (dioxide oxide)) silica siO siO2 sio?sub.2)) and (root near	USPAT;	2002/12/27 09:23
		mean near square near surface near roughness)) not ((((silicon near	US-PGPUB;	
		(dioxide oxide)) silica siO siO2 sio?sub.2) same (layer coating)) and (root	EPO; JPO;	
112	70.40	near mean near square near surface near roughness)) (((ailion near (dioxide exide)) silion siQ siQ2 sig2sub 2) same (layer	DERWENT	2002/12/27 00:20
	7048	(((silicon near (dioxide oxide)) silica siO siO2 sio?sub.2) same (layer coating)) and (surface near roughness)	USPAT; US-PGPUB;	2002/12/27 09:30
		Coating)) and (surface near roughness)	EPO; JPO;	
			DERWENT	
113	2297	((((silicon near (dioxide oxide)) silica siO siO2 sio?sub.2) same (layer	USPAT;	2002/12/27 10:16
		coating)) and (surface near roughness)) and (vapor near (deposition	US-PGPUB;	
		deposited deposit depositing))	EPO; JPO;	
			DERWENT	

		·		
114	17	((((((silicon near (dioxide oxide)) silica siO siO2 sio?sub.2) same (layer	USPAT;	2002/12/27 09:57
		coating)) and (surface near roughness)) and (vapor near (deposition	US-PGPUB;	
		deposited deposit depositing))) and (alkylchlorosilane	EPO; JPO;	
		dimethyldichlorosilane trimethylchlorosilane CH32Cl2Si CH32SiCl2	DERWENT	
		CH3cl3Si ch3sicl3 (ch?sub.3 near ?sub.2 near cl?sub.2 near Si) (ch?sub.3		
		near ?sub.2 near si near cl?sub.2) (ch?sub.3 near cl?sub.3 near si)		
		(ch?sub.3 near si near cl?sub.3))		
115	103	((sicl4 sicl?sub.4 (silicon near tetrachloride)) same (vapor gas)) and	USPAT;	2002/12/27 10:16
		(((((silicon near (dioxide oxide)) silica siO siO2 sio?sub.2) same (layer	US-PGPUB;	
		coating)) and (surface near roughness)) and (vapor near (deposition	EPO; JPO;	
		deposited deposit depositing)))	DERWENT	
116	99	(((sicl4 sicl?sub.4 (silicon near tetrachloride)) same (vapor gas)) and	USPAT;	2002/12/27 10:17
		(((((silicon near (dioxide oxide)) silica siO siO2 sio?sub.2) same (layer	US-PGPUB;	
		coating)) and (surface near roughness)) and (vapor near (deposition	EPO; JPO;	
		deposited deposit depositing)))) not ((((sicl4 sicl?sub.4 (silicon near	DERWENT	
		tetrachloride)) same (vapor gas)) same ((relative near humifity) rh!))		
		(428/426,446,447.ccls. and ((((silicon near (dioxide oxide)) siO siO2		
		sio?sub.2) same (layer coating)) same (humidity rh))) (((sicl4 sicl?sub.4		
		(silicon near tetrachloride)) same (vapor gas)) same ((humidity) rh!))		
		((((sicl4 sicl?sub.4 (silicon near tetrachloride)) same (vapor gas)) same		
		((humidity) rh!)) not (((sicl4 sicl?sub.4 (silicon near tetrachloride)) same		
		(vapor gas)) same ((relative near humifity) rh!))) (428/426,446,447.ccls.		
		and ((((silicon near (dioxide oxide)) silica siO siO2 sio?sub.2) same		
		(layer coating)) same haze)) ((((silicon near (dioxide oxide)) silica siO		
		siO2 sio?sub.2)) and (root near mean near square near surface near		
		roughness)) ((((silicon near (dioxide oxide)) silica siO siO2 sio?sub.2)		
		same (layer coating)) and (root near mean near square near surface near		
		roughness)) (((((silicon near (dioxide oxide)) silica siO siO2 sio?sub.2))		
		and (root near mean near square near surface near roughness)) not		
		((((silicon near (dioxide oxide)) silica siO siO2 sio?sub.2) same (layer		
	:	coating)) and (root near mean near square near surface near roughness)))		
		((((((silicon near (dioxide oxide)) silica siO siO2 sio?sub.2) same (layer coating)) and (surface near roughness)) and (vapor near (deposition		
		deposited deposit depositing))) and (alkylchlorosilane		
		dimethyldichlorosilane trimethylchlorosilane CH32Cl2Si CH32SiCl2		
		CH3cl3Si ch3sicl3 (ch?sub.3 near ?sub.2 near cl?sub.2 near Si) (ch?sub.3		
		near ?sub.2 near si near cl?sub.2) (ch?sub.3 near cl?sub.3 near si)		
		(ch?sub.3 near si near cl?sub.3))))		
-	276323	polysiloxane organopolysiloxane polyorganosiloxane	USPAT;	2002/01/04 06:57
	270323	polydiorganosiloxane diorganopolysiloxane silicone	US-PGPUB;	2002/01/04 00.57
		polydiol gailosilo kaile diol gailo polysilo kaile silicolle	EPO; JPO;	
			DERWENT	
_	6	(("5846649") or ("5618619") or ("5508368") or ("6077569") or	USPAT	2002/12/19 12:24
		("6416816") or ("6245387")).PN.	551711	2302/12/17 12.24
-	0	wo-0025938-\$.did.	USPAT;	2002/12/19 12:24
			US-PGPUB;	12
			EPO; JPO;	
			DERWENT	
-	0	wo-00025938-\$.did.	USPAT;	2002/12/19 12:24
			US-PGPUB;	
			EPO; JPO;	
			DERWENT	
				I
-	0	wo-25938-\$.did.	USPAT;	2002/12/19 12:31
-	0	wo-25938-\$.did.	USPAT; US-PGPUB;	2002/12/19 12:31
-	0	wo-25938-\$.did.	-	2002/12/19 12:31
-	0	wo-25938-\$.did.	US-PGPUB;	2002/12/19 12:31
-	0	wo-25938-\$.did. wo-025938-\$.did.	US-PGPUB; EPO; JPO;	2002/12/19 12:31
-	-		US-PGPUB; EPO; JPO; DERWENT	
-	-		US-PGPUB; EPO; JPO; DERWENT USPAT;	
-	-		US-PGPUB; EPO; JPO; DERWENT USPAT; US-PGPUB;	
-	-		US-PGPUB; EPO; JPO; DERWENT USPAT; US-PGPUB; EPO; JPO;	
-	0	wo-025938-\$.did.	US-PGPUB; EPO; JPO; DERWENT USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/12/19 12:31
-	0	wo-025938-\$.did.	US-PGPUB; EPO; JPO; DERWENT USPAT; US-PGPUB; EPO; JPO; DERWENT USPAT;	2002/12/19 12:31

-	0	2000wo-0025938.ap.	USPAT; US-PGPUB;	2002/12/19 12:33
			EPO; JPO;	
			DERWENT	
l <u>-</u>	131	"25938"	USPAT;	2002/12/19 12:36
			US-PGPUB;	2002/12/12/12/0
			EPO; JPO;	
			DERWENT	
_	7761	428/426,446,447.ccls.	USPAT;	2002/12/19 12:37
	','	120, 120, 110, 117.0013.	US-PGPUB;	2002/12/17 12:37
			EPO; JPO;	
			DERWENT	
<u>-</u>	161140	((silicon near (dioxide oxide)) siO siO2 sio?sub.2) same (layer coating)	USPAT;	2002/12/19 12:45
		((control norm (archive control)) and one provided in the committee of the	US-PGPUB;	
			EPO; JPO;	
			DERWENT	
1_	1327	(((silicon near (dioxide oxide)) siO siO2 sio?sub.2) same (layer coating))	USPAT;	2002/12/19 12:49
	132,	and haze	US-PGPUB;	2002/12/17 12.47
		and nazy	EPO; JPO;	
			DERWENT	
_	9620	(((silicon near (dioxide oxide)) siO siO2 sio?sub.2) same (layer coating))	USPAT;	2002/12/19 12:49
	,020	and (humidity rh)	US-PGPUB;	
			EPO; JPO;	
			DERWENT	
_	145	428/426,446,447.ccls. and ((((silicon near (dioxide oxide)) siO siO2	USPAT;	2002/12/19 12:50
	113	sio?sub.2) same (layer coating)) and haze)	US-PGPUB;	2002/12/17 12.50
		Sio. Suo. 2) Suine (layer conting)) and naze)	EPO; JPO;	
			DERWENT	
_	352	428/426,446,447.ccls. and ((((silicon near (dioxide oxide)) siO siO2	USPAT;	2002/12/27 08:02
	332	sio?sub.2) same (layer coating)) and (humidity rh))	US-PGPUB;	2002/12/27 08.02
		310.340.2) Sume (tayer conting), and (numberly fit))	EPO; JPO;	
			DERWENT	
_	47	(((silicon near (dioxide oxide)) siO siO2 sio?sub.2) same (layer coating))	USPAT;	2002/12/19 12:47
	',	and (root near mean near square near surface near roughness)	US-PGPUB;	2002/12/17 12.47
		and (root near mean near square near surface near roughness)	EPO; JPO;	
			DERWENT	
-	256721	((silicon near (dioxide oxide)) silica siO siO2 sio?sub.2) same (layer	USPAT;	2002/12/19 12:46
		coating)	US-PGPUB;	2002/12/17 12:10
			EPO; JPO;	
			DERWENT	
_	7037	(((silicon near (dioxide oxide)) silica siO siO2 sio?sub.2) same (layer	USPAT;	2002/12/27 09:28
		coating)) and (surface near roughness)	US-PGPUB;	
		<i>(, , , , , , , , , , , , , , , , , , , </i>	EPO; JPO;	
			DERWENT	
-	2839	(((silicon near (dioxide oxide)) silica siO siO2 sio?sub.2) same (layer	USPAT;	2002/12/19 12:49
		coating)) and haze	US-PGPUB;	
			EPO; JPO;	
			DERWENT	
-	19608	(((silicon near (dioxide oxide)) silica siO siO2 sio?sub.2) same (layer	USPAT;	2002/12/27 07:55
		coating)) and (humidity rh)	US-PGPUB;	
			EPO; JPO;	
			DERWENT	
-	193	428/426,446,447.ccls. and ((((silicon near (dioxide oxide)) silica siO	USPAT;	2002/12/19 12:50
		siO2 sio?sub.2) same (layer coating)) and (surface near roughness))	US-PGPUB;	
			EPO; JPO;	
]			DERWENT	
-	258	428/426,446,447.ccls. and ((((silicon near (dioxide oxide)) silica siO	USPAT;	2002/12/27 08:20
		siO2 sio?sub.2) same (layer coating)) and haze)	US-PGPUB;	
		, , , , , , , , , , , , , , , , , , , ,	EPO; JPO;	
			DERWENT	
	605	428/426,446,447.ccls. and ((((silicon near (dioxide oxide)) silica siO	USPAT;	2002/12/19 12:50
		siO2 sio?sub.2) same (layer coating)) and (humidity rh))	US-PGPUB;	12.20
		, (,), (,),	EPO; JPO;	
			DERWENT	
	<u> </u>	I		

-	16	(428/426,446,447.ccls. and ((((silicon near (dioxide oxide)) silica siO siO2 sio?sub.2) same (layer coating)) and (surface near roughness))) and (428/426,446,447.ccls. and ((((silicon near (dioxide oxide)) silica siO siO2 sio?sub.2) same (layer coating)) and haze)) and (428/426,446,447.ccls. and ((((silicon near (dioxide oxide)) silica siO siO2 sio?sub.2) same (layer coating)) and (humidity rh)))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/12/19 12:50
-	61	(((silicon near (dioxide oxide)) silica siO siO2 sio?sub.2) same (layer coating)) and (root near mean near square near surface near roughness)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/12/27 09:21
-	15	((428/426,446,447.ccls. and ((((silicon near (dioxide oxide)) silica siO siO2 sio?sub.2) same (layer coating)) and (surface near roughness))) and (428/426,446,447.ccls. and ((((silicon near (dioxide oxide)) silica siO siO2 sio?sub.2) same (layer coating)) and haze)) and (428/426,446,447.ccls. and ((((silicon near (dioxide oxide)) silica siO siO2 sio?sub.2) same (layer coating)) and (humidity rh)))) not ((((silicon near (dioxide oxide)) silica siO siO2 sio?sub.2) same (layer coating)) and (root near mean near square near surface near roughness))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/12/19 12:51